

Complete set of claims

1(original). A photosensitive composition for an interlayer insulation film, characterized by comprising: a modified polysilsesquiazane having a weight average molecular weight of 500 to 200,000 comprising basic constitutional units represented by formula $-\text{SiR}^1(\text{NR}^2)_{1.5}-$ wherein R^1 's each independently represent an alkyl group having 1 to 3 carbon atoms or a substituted or unsubstituted phenyl group; R^2 's each independently represent hydrogen, an alkyl group having 1 to 3 carbon atoms, or a substituted or unsubstituted phenyl group, up to 50% by mole of said basic constitutional units having been replaced by a linking group other than the silazane bond; and a photoacid generating agent.

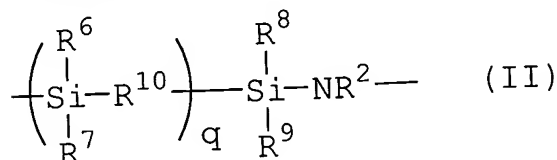
2(original). The photosensitive composition for an interlayer insulation film according to claim 1, wherein said modified polysilsesquiazane further comprises 0.1 to 100% by mole, based on said basic constitutional units, of other constitutional units represented by formula $-\text{SiR}^3_2\text{NR}^2-$ and/or $[\text{SiR}^3_3(\text{NR}^2)_{0.5}]$ wherein R^3 's each independently represent hydrogen, an alkyl group having 1 to 3 carbon atoms, or a substituted or unsubstituted phenyl group; and R^2 's each independently represent hydrogen, an alkyl group having 1 to 3 carbon atoms, or a substituted or unsubstituted phenyl group.

3(currently amended). The photosensitive composition for an interlayer insulation film according to claim 1 or 2, wherein said linking group is represented by formula (I):



wherein R⁴ and R⁵ each independently represent hydrogen, or an alkyl, alkenyl, cycloalkyl, aryl, aralkyl, alkylamino, alkylsilyl, or alkoxy group; and p is an integer of 1 to 10.

4(currently amended). The photosensitive composition for an interlayer insulation film according to claim 1 ~~or 2~~, wherein said linking group is represented by formula (II):



wherein R⁶, R⁷, R⁸, and R⁹ each independently represent an alkyl, alkenyl, cycloalkyl, aryl, aralkyl, alkylamino, alkylsilyl, or alkoxy group; R¹⁰ represents an oxygen atom or an alkylene, alkenylene, cycloalkylene, arylene, alkylimino, or alkylsilylene group; R²'s each independently represent hydrogen, an alkyl group having 1 to 3 carbon atoms, or a substituted or unsubstituted phenyl group; and q is an integer of 1 to 10.

5(original). The photosensitive composition for an interlayer insulation film according to claim 4, wherein R⁶, R⁷, R⁸, and R⁹ represent a methyl group, R¹⁰ represents a phenylene group, R² represents hydrogen, and q is 1.

6(currently amended). The photosensitive composition for an interlayer insulation film according to ~~any one of claims 1 to 5~~ claim 1, wherein said photoacid generating agent is selected from the group consisting of sulfoxime compounds and triazine compounds.

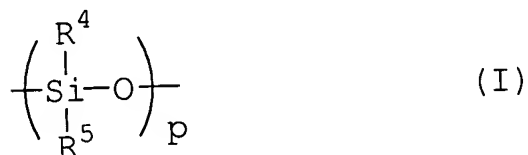
7(currently amended). The photosensitive composition for an interlayer insulation film according to ~~any one of claims 1 to 5~~ claim 1, which further comprises 0.1 to 40% by mass, based on the photosensitive composition, of a dissolution preventive selected from the group consisting of t-butoxycarbonylated catechol, t-butoxycarbonylated hydroquinone, di-t-butyl benzophenone-4,4'-dicarboxylate, and di-t-butyl 4,4'-oxydibenzolate.

8(currently amended). The photosensitive composition for an interlayer insulation film according to ~~any one of claims 1 to 5~~ claim 1, which further comprises a nitro- or carbonic ester-containing water-soluble compound as a shape stabilizer.

9(currently amended). The photosensitive composition for an interlayer insulation film according to ~~any one of claims 1 to 5~~ claim 1, which further comprises a sensitizing dye.

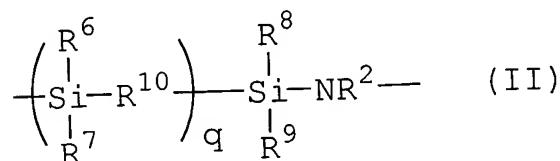
10(original). A method for forming a patterned interlayer insulation film, characterized by comprising: forming a coating of a photosensitive composition for an interlayer insulation film, comprising a modified polysilsesquiazane and a photoacid generating agent, said modified polysilsesquiazane having a weight average molecular weight of 500 to 200,000 comprising basic constitutional units represented by formula - $[\text{SiR}^1(\text{NR}^2)_{1.5}]$ - wherein R^1 's each independently represent an alkyl group having 1 to 3 carbon atoms or a substituted or unsubstituted phenyl group, R^2 's each independently represent hydrogen, an alkyl group having 1 to 3 carbon atoms, or a substituted or unsubstituted phenyl group, up to 50% by mole of said basic constitutional units having been replaced by a linking group other than a silazane bond; exposing said coating pattern-wise to light; dissolving and removing the coating in its exposed area; and subjecting the resultant patterned coating in an ambient atmosphere to standing or baking.

11(new). The photosensitive composition for an interlayer insulation film according to claim 2, wherein said linking group is represented by formula (I):



wherein R⁴ and R⁵ each independently represent hydrogen, or an alkyl, alkenyl, cycloalkyl, aryl, aralkyl, alkylamino, alkylsilyl, or alkoxy group; and p is an integer of 1 to 10.

12(new). The photosensitive composition for an interlayer insulation film according to claim 2, wherein said linking group is represented by formula (II):



wherein R⁶, R⁷, R⁸, and R⁹ each independently represent an alkyl, alkenyl, cycloalkyl, aryl, aralkyl, alkylamino, alkylsilyl, or alkoxy group; R¹⁰ represents an oxygen atom or an alkylene, alkenylene, cycloalkylene, arylene, alkylimino, or alkylsilylene group; R²'s each independently represent hydrogen, an alkyl group having 1 to 3 carbon atoms, or a substituted or unsubstituted phenyl group; and q is an integer of 1 to 10.